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Di-*t*-butylsilyl Bis(trifluoromethanesulfonate)



[85272-31-7] $\text{C}_{10}\text{H}_{18}\text{F}_6\text{O}_6\text{S}_2\text{Si}$ (MW 440.44)

(reagent for the protection of diols)

Physical Data: bp 73–75 °C/0.35 mmHg; d 1.208 g cm⁻³.

Solubility: sol most common organic solvents.

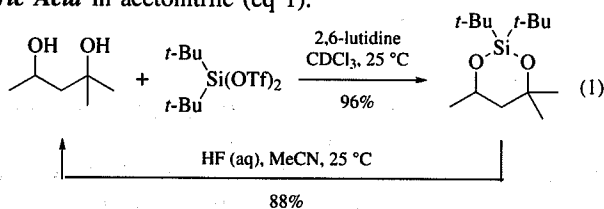
Form Supplied in: liquid.

Preparative Method: by the treatment of di-*t*-butylchlorosilane with **Trifluoromethanesulfonic Acid**, followed by distillation (71% yield).¹

Purification: distillation.

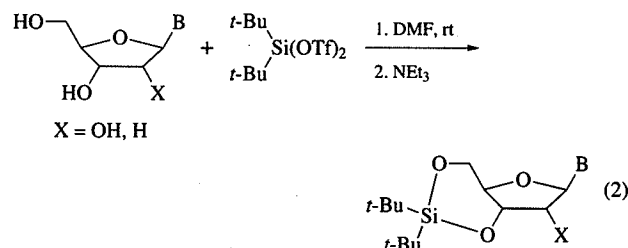
Handling, Storage, and Precautions: moisture sensitive; reacts with hydroxylic solvents; corrosive.

Protection of Alcohols. Di-*t*-butylsilyl bis(trifluoromethanesulfonate) is a reagent for the selective protection of polyhydroxy compounds. This reagent reacts with 1,2-, 1,3-, and 1,4-diols under mild conditions to give the corresponding dialkylsilylene derivatives in high yield (0–50 °C, 79–96%). Deprotection is conveniently achieved by using aqueous **Hydrofluoric Acid** in acetonitrile (eq 1).

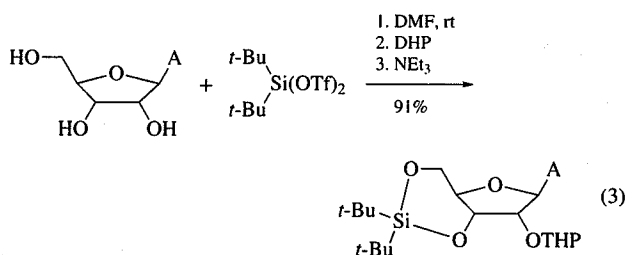


Unlike **Di-*t*-butyldichlorosilane**, this reagent reacts with hindered alcohols. Even pinacol reacts to give the silylene derivative (100 °C, 24 h, 70%). Di-*t*-butylsilylene derivatives of 1,2-diols are more reactive than those of 1,3- and 1,4-diols and undergo rapid hydrolysis (5 min) in THF/H₂O at pH 10, while the 1,3- and 1,4-derivatives are unaffected at pH 4–10 (22 °C) for several hours. This protecting group is stable under the conditions of PDC oxidation of alcohols (CH₂Cl₂, 25 °C, 27 h) and tosylation of alcohols (pyridine, 25 °C, 27 h).

The reagent has seen limited use for the protection of alcohols but has been used to protect nucleosides (eq 2).^{2–5} The procedure consists of sequential addition of the ditriflate and **Triethylamine** to the nucleoside in DMF. The choice of solvent is critical.

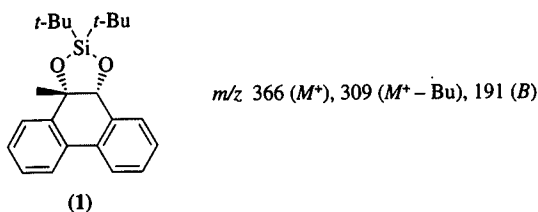


The ribonucleosides of uracil, adenine, and guanine give the protected derivative in 94–95% yield.² Cytidine gives a low yield of the desired product under these conditions. Subsequent studies suggested that O² of cytosine participates in the reaction. Addition of **Trifluoromethanesulfonic Acid** or **Silver(I) Trifluoromethanesulfonate** at 0 °C prior to addition of the silylating agent results in a 99% yield of the desired derivative.³ The derivatives are acid sensitive, presumably due to the proximity of the 2'-hydroxy group. Acetylation, tetrahydropyranylation, methoxytetrahydropyranylation, and silylation of the 2'-hydroxy group are accomplished without affecting the dialkylsilylene protecting group. The 2'-deoxyribonucleosides, including 2'-deoxycytidine, can also be prepared by the aforementioned procedure (yields 90–99%). These cyclic silylene derivatives of nucleosides can be deprotected conveniently using tributylamine hydrofluoride in THF (5 min, 1 M, rt, 20 equiv).⁴ A one-pot procedure has been reported for simultaneously protecting the 2', 3', and 5'-hydroxys of a ribonucleoside, which utilizes the acid generated upon silylating the 3'- and 5'-hydroxys for catalyzing the formation of a THP acetal at the 2'-position (eq 3).⁵

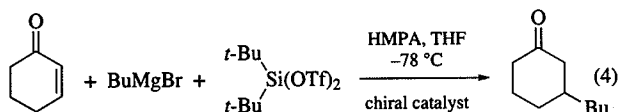


Derivatization of Alcohols. Di-*t*-butylsilyl bis(trifluoromethanesulfonate) has been used to derivatize hindered diols, to give derivatives such as (1), for analysis by gas chromatography–

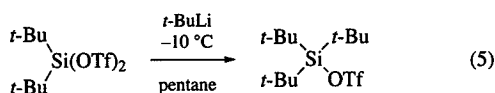
electron impact mass spectrometry.⁶ The major fragmentation is that of the Si-C bonds.



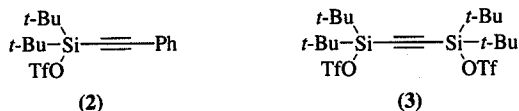
Reagent in Enantioselective Additions. In a study of enantioselective conjugate addition to cyclohexanone it was found that the presence of HMPA and various silyl reagents markedly increases the enantioselectivity (eq 4).⁷ Di-*t*-butylsilyl bis(trifluoromethanesulfonate) gives a 67% yield and 40% ee but *t*-Butyldiphenylchlorosilane gives a 97% yield and 78% ee.



Other Substitution Reactions. An extremely hindered silyl reagent, tri-*t*-butylsilyl trifluoromethanesulfonate, was prepared from di-*t*-butylsilyl bis(trifluoromethanesulfonate) and *t*-Butyllithium (eq 5).⁸ This reagent might find use in the protection of alcohols.



In conjunction with the study of alkyl-substituted silyl triflates, (2) and (3) have been prepared from the corresponding alkynyllithium reagents and di-*t*-butylsilyl bis(trifluoromethanesulfonate).⁹



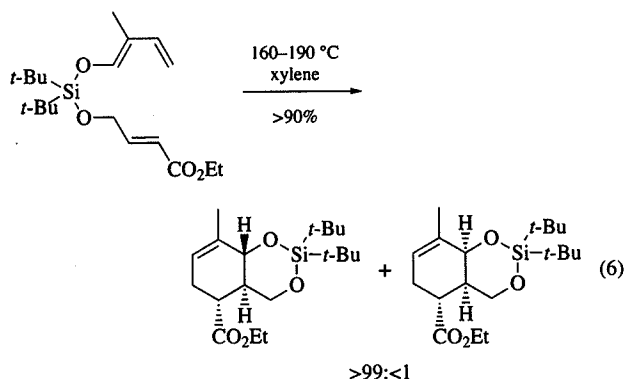
The preparation of other derivatives of di-*t*-butylsilyl bis(trifluoromethanesulfonate) using germanium¹⁰ and phosphorus¹¹ nucleophiles has been reported and provides bifunctional silanes such as (4) and (5).



X = -C≡CPh, -SiPh₃, -N(TMS)₂, -PPh, -O-*i*-Pr, -SPh

A compound closely related to di-*t*-butylsilyl bis(trifluoromethanesulfonate) is di-*t*-butylchlorosilyl trifluoromethanesulfonate, which has been used to tether two structurally different

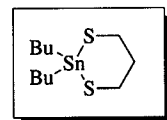
alcohol derivatives in order to effect an intramolecular Diels-Alder reaction (eq 6).¹²



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2,2-Dibutyl-2-stanna-1,3-dithiane¹



[7191-32-4]

C₁₁H₂₄S₂Sn

(MW 339.20)

(reagent for synthesizing 1,3-dithianes from aldehydes and acetals^{2,3})

Alternate Name: DSDT.

Physical Data: mp 63–64 °C; bp 170 °C/0.5 mmHg.

Solubility: insol H₂O; sol most organic solvents.

Analysis of Reagent Purity: ¹H NMR (CDCl₃) δ 0.93 (t, 6H, J = 7.32 Hz), 1.61 (m, 14H), 2.94 (t, 4H, J = 6.10 Hz); ¹³C NMR (CDCl₃) δ 13.40, 24.51, 26.50, 27.82, 30.16.

Preparative Method: to a CH₂Cl₂ solution (400 mL) of Bu₂SnCl₂ (45.8 g, 0.15 mol) and HS(CH₂)₃SH (15.1 mL, 0.15 mol) is added Et₃N (41.8 mL, 0.3 mol) at 0 °C. The solution

Avoid Skin Contact with All Reagents